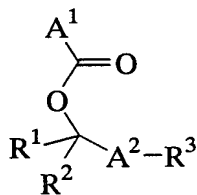


# ABSTRACT

Novel ester compounds having formula (1) wherein A<sup>1</sup> is  
5 a polymerizable functional group having a double bond, A<sup>2</sup> is  
furandiyl, tetrahydrofurandiyl or oxanorbornanediyl, R<sup>1</sup> and  
R<sup>2</sup> each are a monovalent hydrocarbon group, or R<sup>1</sup> and R<sup>2</sup> may  
bond together to form an aliphatic hydrocarbon ring with the  
carbon atom, and R<sup>3</sup> is hydrogen or a monovalent hydrocarbon  
10 group which may contain a hetero atom are polymerizable into  
polymers. Resist compositions comprising the polymers are  
sensitive to high-energy radiation, have an improved  
sensitivity, resolution, and etching resistance, and lend  
themselves to micropatterning with electron beams or deep-UV  
15 rays.



(1)